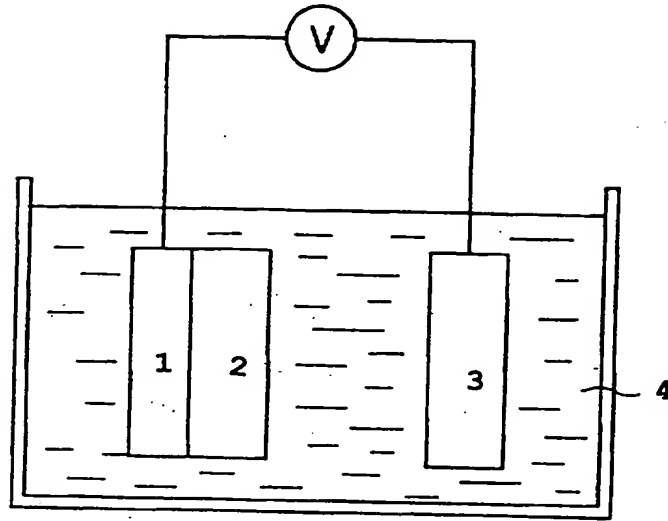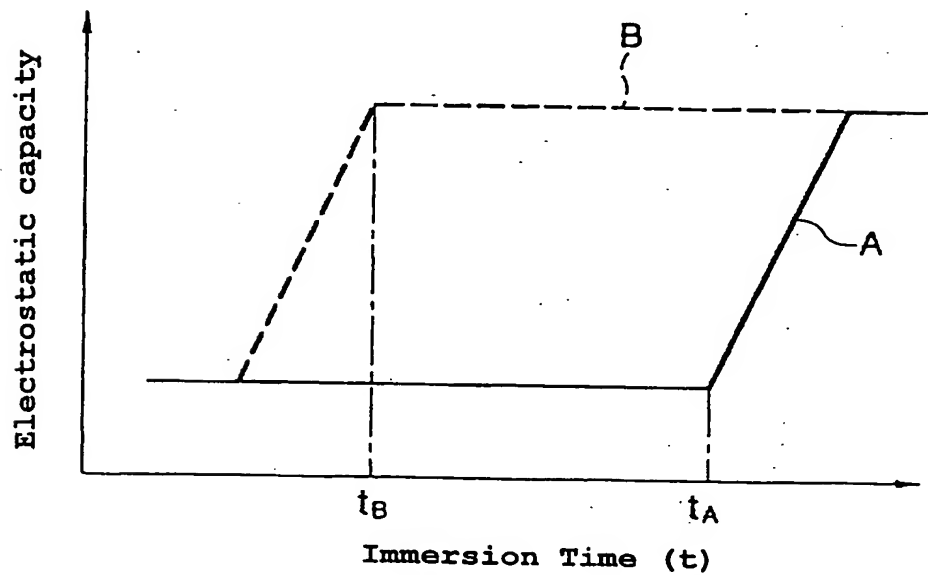## Fig. 1

Fig. 2

B: Photosensitive material in which the developing solution is easily immersed.

t_B: Time in which electrostatic capacity is changed.

A: Photosensitive material in which the developing solution is immersed with difficulty.

T_a: Time in which electrostatic capacity is changed.

Fig. 3

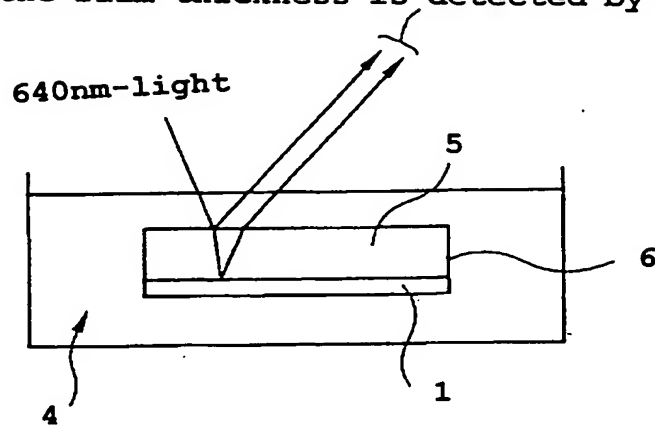**The change of the film thickness is detected by the coherent**

640nm-light

5

6

4

1

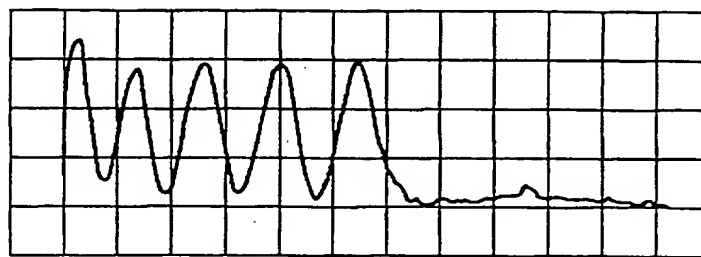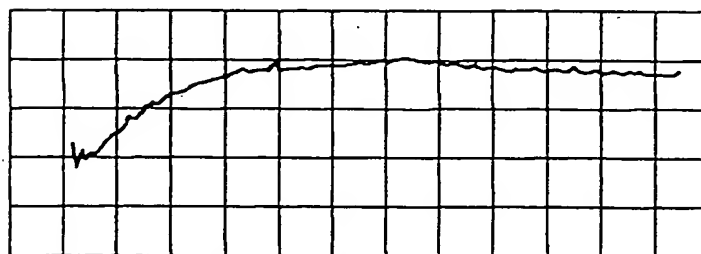## Fig. 4

time

(Coherent Wave o): Invention
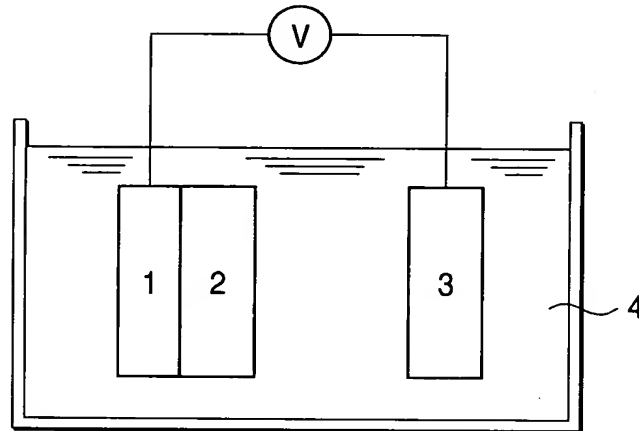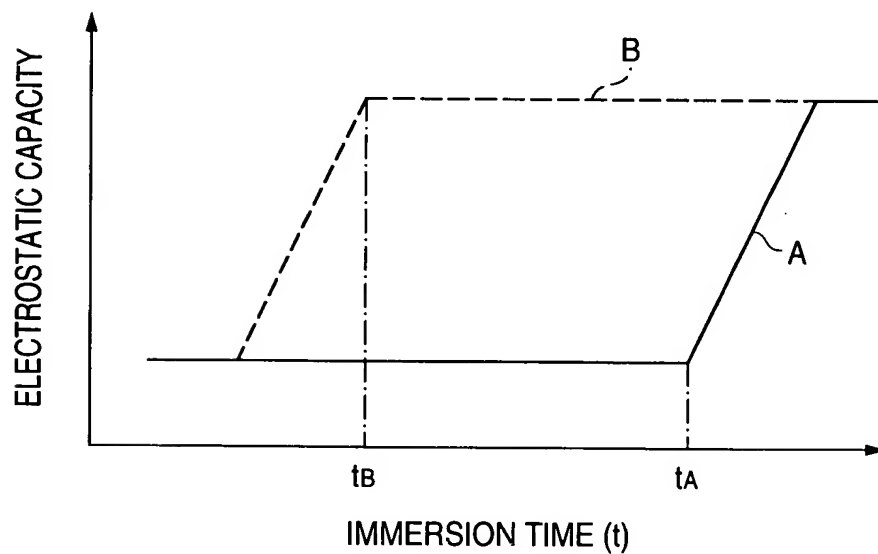
time

(Coherent Wave x): Conventional

FIG. 1

FIG. 2

B: PHOTOSENSITIVE MATERIAL IN WHICH THE DEVELOPING SOLUTION IS EASILY
   IMMERSED
tB: TIME IN WHICH ELECTROSTATIC CAPACITY IS CHANGED
A: PHOTOSENSITIVE MATERIAL IN WHICH THE DEVELOPING SOLUTION IS IMMERSED
   WITH DIFFICULTY
Ta: TIME IN WHICH ELECTROSTATIC CAPACITY IS CHANGED

FIG. 3

THE CHANGE OF THE FILM THICKNESS
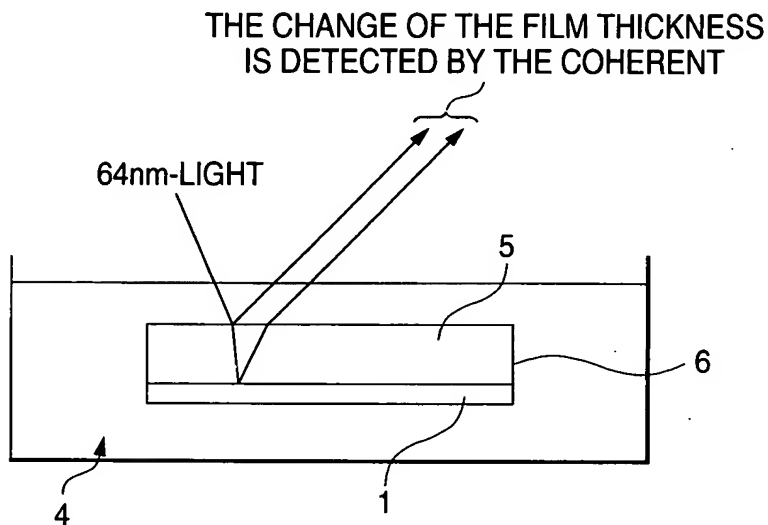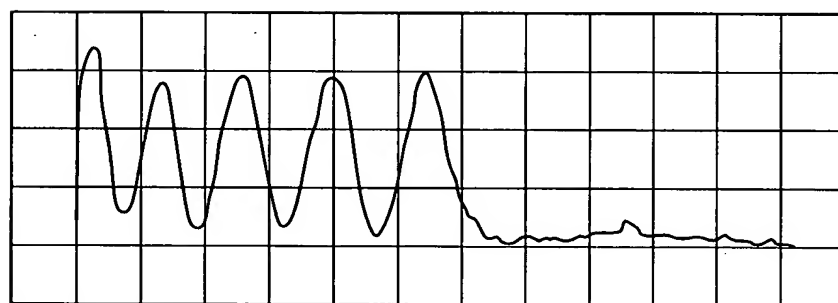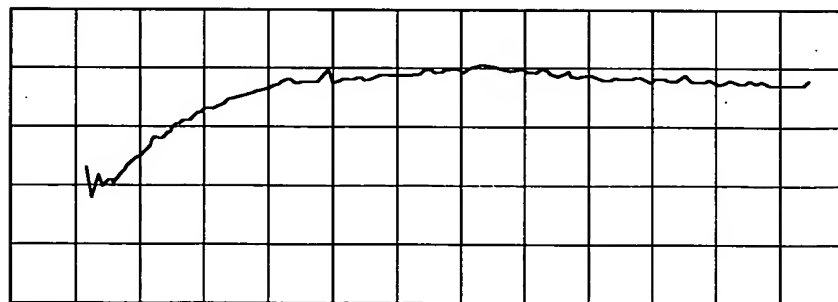IS DETECTED BY THE COHERENT

64nm-LIGHT

FIG. 4

TIME

(COHERENT WAVE o) : INVENTION

TIME

(COHERENT WAVE x) : CONVENTIONAL